

Title (en)

SYSTEM AND METHOD FOR ADJUSTING A MATERIAL BED DEPTH IN A PULVERIZER MILL

Title (de)

SYSTEM UND VERFAHREN ZUR ANPASSUNG EINER MATERIALBETTTIEFE IN EINER PULVERISATORMÜHLE

Title (fr)

SYSTÈME ET PROCÉDÉ PERMETTANT DE RÉGLER UNE PROFONDEUR DE COUCHE DE MATÉRIAU DANS UN BROYEUR PULVÉRISATEUR

Publication

EP 3595816 A1 20200122 (EN)

Application

EP 18710450 A 20180309

Priority

- US 201715457106 A 20170313
- EP 2018055861 W 20180309

Abstract (en)

[origin: US2018257085A1] A system for adjusting a depth of a material bed in a pulverizer mill is provided. The system includes a rotatable bowl, an extension ring, and an extension mechanism. The rotatable bowl has a surface operative to support the material bed while the bowl rotates such that particles of the material bed are pulverized against the surface by one or more grinding rollers of the pulverizer mill. The extension ring is disposed about a circumference of the rotatable bowl extending away from the surface and defines a depth of the material bed. The extension mechanism adjusts at least one of the extension ring and the rotatable bowl while the rotatable bowl rotates. Adjusting at least one of the extension ring and the rotatable bowl via the extension mechanism moves the extension ring in relation to the surface so as to adjust the depth of the material bed.

IPC 8 full level

B02C 15/00 (2006.01)

CPC (source: EP KR US)

B02C 15/001 (2013.01 - KR US); **B02C 15/003** (2013.01 - EP KR US); **B02C 15/007** (2013.01 - US); **B02C 15/045** (2013.01 - KR US); **B02C 25/00** (2013.01 - KR US); **B02C 2015/002** (2013.01 - KR US)

Citation (search report)

See references of WO 2018166903A1

Designated contracting state (EPC)

AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

Designated extension state (EPC)

BA ME

DOCDB simple family (publication)

US 10646877 B2 20200512; **US 2018257085 A1 20180913**; CN 110545919 A 20191206; CN 110545919 B 20230221; EP 3595816 A1 20200122; EP 3595816 B1 20230809; JP 2020509926 A 20200402; JP 7277048 B2 20230518; KR 102504925 B1 20230228; KR 20190126352 A 20191111; PL 3595816 T3 20231030; WO 2018166903 A1 20180920

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US 201715457106 A 20170313; CN 201880016128 A 20180309; EP 18710450 A 20180309; EP 2018055861 W 20180309; JP 2019545930 A 20180309; KR 20197028855 A 20180309; PL 18710450 T 20180309